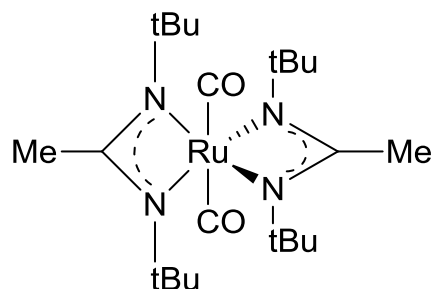


Catalog # 44-0056 Bis(N,N-di-t-butylacetamidato)ruthenium(II) dicarbonyl, 98% (99.99%-Ru) PURATREM



Technical Notes:

1. Precursor used for the CVD and ALD of Ruthenium-containing thin films.¹⁻⁷

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